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Attorney Docket no: ~~SEL 246~~

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TECHNOLOGY CENTER 2800

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )

Koichiro TANAKA )

Serial No.: 09/812,529 )

Filed: March 20, 2001 )

For: Method of Manufacturing A Semiconductor )  
Device )

Examiner: R. Booth )

Art Unit: 2812 )

I hereby certify that this correspondence is being  
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the Assistant Commissioner for Patents, Washington,  
D.C. 20231 on August 28, 2002 *#612*  
(Date of Deposit) *9/16/02*

*Rachelle Hammerquist*  
Name of applicant, assignee, or Registered Rep.  
*Rachelle Hammerquist* 8-18-02  
Signature Date

Commissioner for Patents  
Washington D.C. 20231

AMENDMENT A

In response to the Office Action of March 28, 2002, a two month extension of time being  
separately requested, please amend the above-identified application as follows:

IN THE CLAIMS:

Please amend the claims as follows:

1 (Amended). A method of manufacturing a semiconductor device, comprising:

forming an amorphous semiconductor film over a substrate;

*B1* irradiating the amorphous semiconductor film with a first laser beam to form a first  
crystalline semiconductor film; and

irradiating the first crystalline semiconductor film with a second laser beam to form a second  
crystalline semiconductor film,